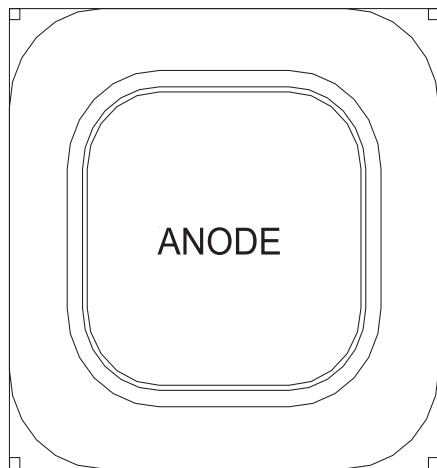


**PROCESS DETAILS**

Process	EPITAXIAL PLANAR
Die Size	14 x 14 MILS
Die Thickness	7.1 MILS
Anode Bonding Pad Area	9.0 x 9.0 MILS
Top Side Metalization	Al - 30,000Å
Back Side Metalization	Au - 12,000Å

**GEOMETRY**



BACKSIDE CATHODE

**GROSS DIE PER 4 INCH WAFER**

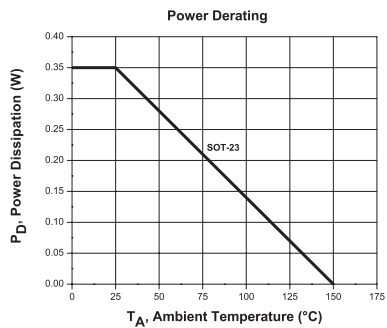
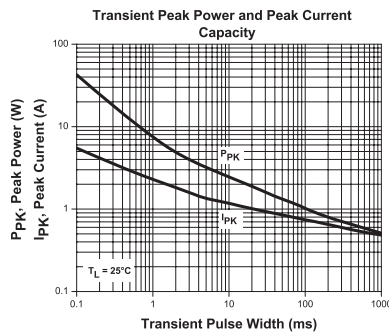
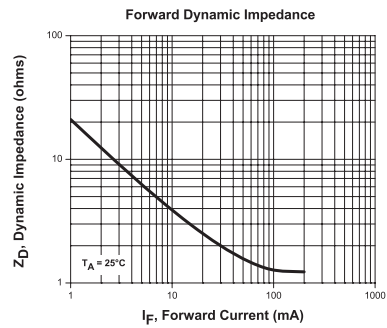
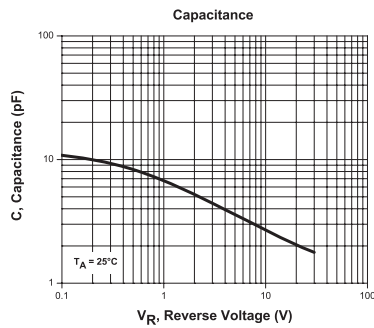
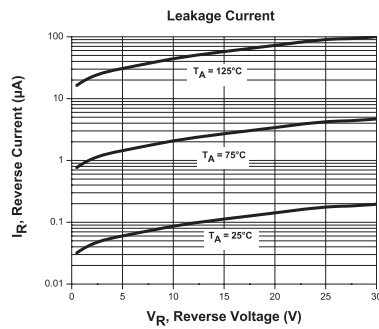
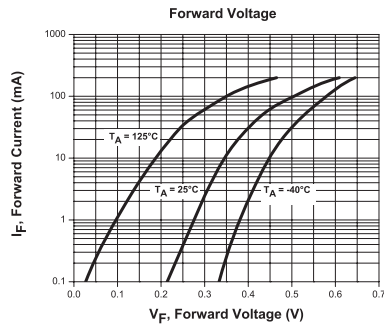
59,940

**PRINCIPAL DEVICE TYPES**

CMP SH-3 Series  
CMSSH-3 Series  
CMXSH-3  
CMKSH-3T

145 Adams Avenue  
Hauppauge, NY 11788 USA  
Tel: (631) 435-1110  
Fax: (631) 435-1824  
www.centalsemi.com

R2 (8-October 2008)



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